

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. - 58. (Cancelled)

59. (Currently Amended) An exposure apparatus, having an exposure light source which generates an exposure beam and an exposure main unit which holds a mask and a substrate, and in which the exposure beam is used to transfer a pattern of the mask onto the substrate, the exposure apparatus comprising:

a first illumination system, supported independently from the exposure main unit, which transmits the exposure beam from the exposure light source; and

a second illumination system, fixed to the exposure main unit, which guides the exposure beam emitted from the first illumination system to the exposure main unit,

wherein a mask blind is disposed in a boundary portion of the first illumination system and the second illumination system.

60. (Previously Added) The exposure apparatus according to claim 59, wherein the optical paths of the exposure beam within the first illumination system and the second illumination system are each substantially sealed, and gas transmissive with respect to the exposure beam is independently supplied to the sealed first and second optical paths.

61. (Currently Amended) The exposure apparatus according to claim 59, wherein a plane of incidence of the exposure beam emitted from the first illumination system on the second illumination system is conjugate with respect to ~~the~~ a pattern formation face of the mask, and ~~that~~ a field stop is positioned in the ~~incidence-plane~~ of incidence.

62. - 66. (Cancelled)

67. (Currently Amended) A method for manufacturing an exposure apparatus, comprising the steps of:

providing an exposure light source which generates an exposure beam;
providing an exposure main unit which holds a mask and a substrate;
providing a first illumination system, supported independently from the exposure main unit, which transmits the exposure beam from the exposure light source; ~~and~~,
providing a second illumination system, fixed to the exposure main unit, which guides the exposure beam emitted from the first illumination system to the exposure main unit; and
providing a mask blind at a boundary portion of the first and second illumination systems.

68. - 75. (Cancelled)

76. (Currently Amended) A device manufacture method comprising a process to transfer the pattern of a mask onto a substrate by using the exposure apparatus of claim 59.

77. (Previously Added) The exposure apparatus according to claim 59, wherein the first illumination system comprises an optical member having a driving mechanism.

78. (Previously Added) The exposure apparatus according to claim 77, wherein the second illumination system comprises an optical member not having a driving mechanism.

79. (Currently Amended) The exposure apparatus according to claim 77, wherein the ~~purpose of the~~ driving mechanism is provided to enable variation of ~~the an~~ illumination shape or ~~the an~~ illumination intensity of the exposure beam illuminating the mask.

80. (Previously Added) The exposure apparatus according to claim 77, wherein the optical member having the driving mechanism includes a movable blind enabling changes to the illumination range of the mask by the exposure beam.

81. (Currently Amended) The exposure apparatus according to claim 80, wherein the mask blind has a fixed blind to fix the illumination range of the mask by the exposure beam, and the fixed blind is provided in the first illumination system.

82. (Previously Added) The exposure apparatus according to claim 77, wherein the optical member having a driving mechanism includes an attenuator which attenuates the exposure beam.

83. (Currently Amended) The exposure apparatus according to claim 59, wherein the exposure main unit has a first support member to support ~~the~~ a projection system which projects an image of ~~an~~ the pattern of the mask onto the substrate, and the second illumination system is fixed to the first support member, and the first illumination system is supported by a second support member independent of the first support member.

84. (Previously Added) The exposure apparatus according to claim 83, wherein the exposure light source is positioned independently of the first support member and of the second support member.

85. (Currently Amended) The exposure apparatus according to claim 83, wherein the first support member and the second support member are each positioned on ~~the same~~ a base, and the exposure light source is positioned independently of the base.

86. (Currently Amended) The ~~exposure~~ method according to claim 67, wherein the first illumination system comprises an optical member having a driving mechanism which is a source of vibrations, and ~~that the~~ second illumination system comprises an optical member not having a driving mechanism which is a source of vibrations.

87. (Currently Amended) An exposure apparatus, having an exposure light source which generates an exposure beam and a first support member which supports a projection

system which projects an image of a pattern of a mask onto a substrate, and in which the exposure beam is used to transfer the pattern of the mask onto the substrate;

the exposure apparatus comprising:

an illumination system which guides the exposure beam from the exposure light source to the mask and which has ~~an a plurality of movable optical member-members~~ each having a driving mechanism; and

a second support member which supports all of the movable optical member-members of the illumination system, independently of the first support member so as not to become a source of vibrations for the first support member.

88. (Previously Added) The exposure apparatus according to claim 87, wherein the illumination system has a first illumination system which includes the optical member having the driving mechanism and a second illumination system which does not include any optical members having driving mechanisms, and

the second illumination system is fixed to the first support member.

89. (Previously Added) The exposure apparatus according to claim 87, wherein the driving mechanism is provided to enable variation of one of an illumination shape and an illumination intensity of the exposure beam illuminating the mask.

90. (Currently Amended) The exposure apparatus according to claim 87, wherein the first support member and the second support member are positioned on ~~the same a~~ a base.

91. (Currently Amended) The exposure apparatus according to claim 87, wherein the exposure light source is positioned independently of the first support member and of the second support member.

92. (Currently Amended) An exposure apparatus which transfer ~~the a~~ a pattern of a mask onto a substrate, using an exposure beam generated by an exposure light source, the apparatus comprising:

~~an illumination system which guides the exposure beam from the exposure light source to the mask; and~~

~~a first illumination unit system, provided within the illumination system, holding a plurality of optical members driven by a driving unit, and in which an optical path of the exposure beam, including the plurality of optical members, is substantially sealed supported independently from an exposure main unit which holds the mask and the substrate, and which transmits the exposure beam from the exposure light source;~~

~~a second illumination system which is fixed to the exposure main unit, and which guides the exposure beam emitted from the first illumination system to the exposure main unit;~~

~~a movable mask blind which is disposed in an emitting plane of the first illumination system, and which enables changes to an illumination range of the mask by the exposure beam; and~~

~~a fixed blind which is disposed in an incidence plane of the second illumination system, and which fixes the illumination range of the mask by the exposure beam.~~

93. (Currently Amended) The exposure apparatus according to claim 92, further comprising a supply device which supplies gas, transmissive with respect to the exposure beam, to ~~the a sealed optical path of the first and second illumination systems.~~

94. (Currently Amended) The exposure apparatus according to claim 92, further comprising ~~a second illumination system unit which guides the exposure beam from the first illumination system unit to the mask,~~ and a first support member which supports the ~~a~~ projection system which projects the image of the pattern of the mask onto the substrate; and wherein

the first illumination system ~~unit~~ is supported by a second support member independent from the first support member, and the second illumination system ~~unit~~ is fixed to the first support member.

95. (Currently Amended) The exposure apparatus according to claim 94, wherein the first support member and the second support member are positioned on ~~the same a~~ base.

96. (Currently Amended) The exposure apparatus according to claim 94, wherein the exposure light source is positioned independently of the first support member and the second support member.

97. (Currently Amended) An exposure method in which an image of a pattern of a mask is transferred onto a substrate via a projection optical system supported by a first supporting member, using the exposure beam which is generated from an exposure light source, the exposure method comprising the steps of:

guiding the exposure beam from the exposure light source to the mask via an illumination system which has ~~an a plurality of movable optical element elements each~~ having a driving mechanism which is a source of vibrations;

supporting ~~all of the movable optical element elements~~ of the illumination system independently from the first support member; and

driving the driving mechanism without transmitting the vibrations to the first support member.

98. (Currently Amended) The exposure method according to claim 97, wherein the driving mechanism is provided to drive the optical ~~member elements~~ to change the illumination conditions of the mask by the exposure beam.

99. (Currently Amended) The exposure method according to claim 97, wherein an optical path within the illumination system containing the optical ~~member elements~~ having

the driving mechanism which is a source of vibration is substantially sealed, and a gas which is transmissive with respect to the exposure beam is supplied to the illumination system.

100. (Previously Added) A device manufacturing method comprising a process in which the pattern of a mask is transferred to a substrate, using the exposure apparatus of claim 87.

101. (New) A device manufacturing method comprising a process in which the pattern of a mask is transferred to a substrate using the exposure method of claim 97.